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Contents

- ix *Symposium Committees*
- xi *Conference Committee*
- xiii *Quantum dot lasers and relevant nanoheterostructures (Plenary Paper) [8552-1]*
A. E. Zhukov, N. V. Kryzhanovskaya, A. V. Savelyev, A. M. Nadtochiy, E. M. Arakcheeva, F. I. Zubov, V. V. Korenev, Saint Petersburg Academic Univ. (Russian Federation); M. V. Maximov, Y. M. Shernyakov, M. M. Kulagina, I. A. Slovinskiy, Ioffe Physical-Technical Institute (Russian Federation); D. A. Livshits, Innolume GmbH (Germany); A. Kapsalis, C. Mesaritakis, D. Syvridis, Univ. of Athens (Greece); A. M. Mintairov, Univ. of Notre Dame (United States)

PLASMONIC AND NANO MATERIALS/DEVICES I

- 8555 02 **Optical interaction between silver nanocubes and two-dimensional silver gratings studied by surface enhanced Raman scattering [8555-3]**
Q. Fu, D. Zhang, Y. Chen, P. Wang, H. Ming, Univ. of Science and Technology of China (China)
- 8555 03 **Making the mid-infrared nano with designer plasmonic materials (Invited Paper) [8555-1]**
S. Law, J. Felts, Univ. of Illinois at Urbana-Champaign (United States); C. Roberts, V. A. Podolskiy, Univ. of Massachusetts Lowell (United States); W. P. King, D. Wasserman, Univ. of Illinois at Urbana-Champaign (United States)
- 8555 04 **Polymer based plasmonic elements with dye molecules (Invited Paper) [8555-2]**
D. Zhang, X. Wang, Y. Chen, L. Han, P. Wang, H. Ming, Univ. of Science and Technology of China (China)
- 8555 05 **Subwavelength dielectric-loaded plasmonic waveguides based on a core-shell structure [8555-4]**
B. Shen, Y. Huang, X. Ren, Q. Wang, X. Zhang, X. Duan, D. Zhang, J. Hu, Beijing Univ. of Posts and Telecommunications (China)

PLASMONIC AND NANO MATERIALS/DEVICES II

- 8555 08 **A simple ultra-wideband dual-core SPSM PCF [8555-7]**
M. Liu, D. Li, Chongqing Univ. (China)
- 8555 09 **Compact terahertz wave broadband reflectors based on silicon photonic crystal slabs [8555-9]**
X. Hao, Z. Qiang, Z. Chen, Y. Zheng, J. Jiang, Fujian Normal Univ. (China); X. Chen, Minjiang Univ. (China); Y. Qiu, Fujian Normal Univ. (China)

- 8555 0B **Absorption modulation enhancement of Azo-polymer film induced by plasmonic field** [8555-10]
X. Wang, Univ. of Science and Technology of China (China) and ChaoHu College (China);
D. Zhang, Q. Fu, H. Ming, W. Wu, Q. Zhang, Univ. of Science and Technology of China
(China)

FIBER AND GUIDED-WAVE LASERS/SEMICONDUCTOR DEVICES I

- 8555 0D **Transverse modes switchable fiber laser based on few-mode fiber Bragg grating** [8555-13]
B. Sun, A. Wang, Y. Zhou, C. Gu, Z. Lin, L. Xu, H. Ming, Univ. of Science and Technology of
China (China)
- 8555 0E **Emission properties of single deep confinement potential QD-cavity system under
incoherent excitation** [8555-15]
H. Guan, P. Yao, W. Yu, P. Wang, H. Ming, Univ. of Science and Technology of China
(China)
- 8555 0F **External cavity based single mode Fabry-Pérot laser diode and its application towards all-
optical digital circuits (Invited Paper)** [8555-12]
B. Nakarmi, Korea Advanced Institute of Science and Technology (Korea, Republic of) and
Nanjing Univ. (China); X. Zhang, Nanjing Univ. (China); Y. H. Won, Korea Advanced Institute
of Science and Technology (Korea, Republic of)
- 8555 0G **Research on pattern-induced transparent conductive films** [8555-14]
X. Zhou, Z. Fang, H. Zhang, L. Chen, Soochow Univ. (China)

FIBER AND GUIDED-WAVE LASERS/SEMICONDUCTOR DEVICES II

- 8555 0H **Tunable high-power multi-wavelength double-clad fiber laser** [8555-18]
J. You, X. Wang, P. Xiao, L. Huang, National Univ. of Defense Technology (China)
- 8555 0I **Opto-DMD -based tunable triple-channel-wavelength fiber laser** [8555-17]
D. Zhang, B. Yan, K. Huang, Q. Yang, Beijing Univ. of Posts and Telecommunications
(China); X. Chen, Minzu Univ. of China (China); G. Chen, Beijing Jiaotong Univ. (China);
X. Sang, Beijing Univ. of Posts and Telecommunications (China)
- 8555 0J **All-optical QPSK signal regeneration based on XPM in semiconductor optical amplifier**
[8555-19]
Y. Zhan, M. Zhang, M. Liu, Z. Liu, X. Chen, Beijing Univ. of Posts and Telecommunications
(China)

FIBER AND GUIDED-WAVE LASERS/SEMICONDUCTOR DEVICES III

- 8555 0K **Optical generation of millimeter-wave based on single-mode fiber ring cavity** [8555-24]
H. Chen, L. Chen, C. Chen, Yangtze Univ. (China)

- 8555 ON **All-optical modulation based on side mode injection locked multi-mode Fabry-Pérot laser diode (Invited Paper)** [8555-20]
J.-W. Wu, Chongqing Normal Univ. (China) and Hohai Univ. (China); B. Nakarmi, KAIST (Korea, Republic of)

POSTER SESSION

- 8555 OP **Analysis and design of a tunable filtering waveguide based on silicon-on-insulator** [8555-55]
F. Hu, Y. Huang, X. Duan, X. Zhang, X. Fan, X. Ren, Q. Wang, X. Zhang, S. Cai, J. Hu, Beijing Univ. of Posts and Telecommunications (China)
- 8555 OR **Blue-green reflection-mode GaAlAs photocathodes** [8555-70]
X. Chen, J. Zhao, B. Chang, M. Jin, G. Hao, Y. Xu, Nanjing Univ. of Science and Technology (China)
- 8555 OU **Add-drop filters based on asymmetric high-order microring resonators** [8555-51]
D. Zhang, Y. Huang, X. Ren, X. Duan, B. Shen, Q. Wang, X. Zhang, S. Cai, Beijing Univ. of Posts and Telecommunications (China)
- 8555 OV **Coplanar lumped electroabsorption modulator fabricated on the common n-type InP substrate** [8555-57]
C. Zhang, S. Liang, L. Ma, B. Wang, H. Zhu, W. Wang, Institute of Semiconductors (China)
- 8555 OX **A flat-top steep-edge waveguide photodetector composed of cascaded silicon microring resonators** [8555-59]
J. Hu, Y. Huang, X. Duan, X. Fan, F. Hu, L. Yang, B. Shen, Q. Wang, X. Zhang, X. Ren, Beijing Univ. of Posts and Telecommunications (China)
- 8555 OY **Selective etching of GaAs/Si and InP/GaAs heteroepitaxial wafer** [8555-78]
X. Zhen, Q. Wang, Z.-G. Jia, Y.-Q. Huang, X.-M. Ren, Beijing Univ. of Posts and Telecommunications (China)
- 8555 OZ **1.65 μ m three-section Distributed Bragg Reflective (DBR) laser for CH₄ gas sensor** [8555-74]
B. Niu, H. Yu, L. Yu, D. Zhou, L. Zhao, J. Pan, W. Wang, Institute of Semiconductors (China)
- 8555 10 **A photonic instantaneous microwave frequency measurement with improved range and accuracy** [8555-63]
N. Shi, X. Han, Y. Gu, J. Hu, M. Wang, M. Zhao, Dalian Univ. of Technology (China)
- 8555 11 **The influence of growth parameters on the formation on InAs/GaAs by MOCVD** [8555-56]
H. Wang, Q. Wang, Z.-G. Jia, Y.-C. Yan, Y.-Q. Huang, X.-M. Ren, Beijing Univ. of Posts and Telecommunications (China)
- 8555 12 **Saturable absorption in graphene at 800-nm band** [8555-75]
S. Lu, S. Chen, Z. Zheng, H. Zhang, C. Zhao, S. Wen, Hunan Univ. (China)
- 8555 15 **Direct-detection WiMax orthogonal frequency division multiplexing over fiber access networks** [8555-72]
J. He, National Univ. of Defense Technology (China) and Hunan Univ. (China); J. Su, National Univ. of Defense Technology (China); Y. Huang, H. Liu, Hunan Univ. (China)

- 8555 16 **Hermite Gaussian approximation for TE₁ mode of dielectric planar waveguide** [8555-54]
Z. Wang, L. Li, F. Guo, Fujian Normal Univ. (China)
- 8555 17 **The tunable demodulator of DPSK based on reflection differential delay interference**
[8555-60]
G. Liu, C. Wu, Y. Mao, Z. Li, Beijing Jiaotong Univ. (China)
- 8555 18 **Simulation and parameters optimization of high gain silicon micro-pixel avalanche photodiode** [8555-69]
F. Sun, H. Gu, Z. Wang, L. Chen, Harbin Institute of Technology (China)
- 8555 19 **Liquid crystal microlens with tunable-focus over focal plane driven by low-voltage signal**
[8555-39]
S. Kang, Huazhong Univ. of Science and Technology (China) and Wuhan Polytechnic Univ. (China); X. Rong, X. Zhang, C. Xie, T. Zhang, Huazhong Univ. of Science and Technology (China)
- 8555 1A **A no adhesive and temperature-insensitive package design of fiber Bragg grating pressure sensor** [8555-40]
H. Wang, J. Zhu, H. Yin, Z. Zhang, H. Tang, B. Yu, Anhui Univ. (China)
- 8555 1B **Linearly-polarized Yb-doped fiber laser based on 45-degree fiber Bragg grating** [8555-41]
S. Fu, X. Liu, L. Guo, X. Ge, G. Wei, Shandong Univ. of Technology (China)
- 8555 1C **Photoemission stability of negative electron affinity GaN photocathode** [8555-42]
J. Zhang, X. Wang, Nanjing Univ. of Science and Technology (China); W. Yang, W. Tang, Xi'an Institute of Optics and Precision Mechanics (China); X. Fu, B. Li, B. Chang, Nanjing Univ. of Science and Technology (China)
- 8555 1F **Giant laser-induced thermoelectric voltage in c-axis inclined Na_xCoO₂ thin films** [8555-47]
S. Wang, H. Wang, S. Chen, Z. Bai, G. Yan, J. Wang, W. Yu, G. Fu, Hebei Univ. (China)
- 8555 1H **Coupling characteristics between fundamental mode square waveguide and fiber**
[8555-49]
F. Guo, L. Li, H. Zheng, Y. Wang, J. Ke, T. Dai, X. Lin, Fujian Normal Univ. (China)
- 8555 1I **Variable doping narrow-band response GaAlAs photocathode the preparation method of the research** [8555-50]
Y. Xu, Nanjing Univ. of Science and Technology (China) and Nanyang Institute of Technology (China); X. Chen, J. Zhao, H. Wang, B. Chang, Nanjing Univ. of Science and Technology (China)
- 8555 1J **Design and fabrication of the Y-branch waveguide for optical printed circuit board (OPCB) interconnect** [8555-61]
K. Li, F. Pang, X. Zhang, T. Wang, Shanghai Univ. (China)
- 8555 1K **Experimental demonstration of a narrow linewidth 1120-nm Yb-doped fiber laser** [8555-52]
X. Liu, S. Fu, K. Han, X. Ge, L. Guo, Shandong Univ. of Technology (China)
- 8555 1L **A polymer-modified PbS quantum dot fiber amplifier excited by evanescent wave**
[8555-58]
X. Sun, L. Xie, W. Zhou, Shanghai Univ. (China)

- 8555 1M **Long distance optical printed circuit board for 10Gbps optical interconnection** [8555-67]
S. Chen, F. Pang, K. Li, Shanghai Univ. (China); J. Wu, Shanghai Meadville Science and Technology Co. Ltd (China); M. Immonen, Meadville Aspocomp International Ltd. (Finland); X. Zhang, T. Wang, Shanghai Univ. (China)
- 8555 1N **Model of a series-cascaded fractal topological structure of microring resonator arrays** [8555-76]
X. Zhang, Y. Li, F. Gu, B. Jin, Shanghai Univ. (China)
- 8555 1O **High stable single-polarization tunable fiber laser based on Opto-DMD processor and polarization-maintaining fiber devices** [8555-62]
K. Huang, B. Yan, Beijing Univ. of Posts and Telecommunications (China); X. Chen, Minzu Univ. of China (China); G. Chen, Beijing Jiaotong Univ. (China); Q. Ai, Minzu Univ. of China (China); K. Wang, Beijing Univ. of Posts and Telecommunications (China); Y. Wang, Y. Zhang, Minzu Univ. of China (China); F. Song, Beijing Univ. of Posts and Telecommunications (China) and Minzu Univ. of China (China); X. Sang, Beijing Univ. of Posts and Telecommunications (China)
- 8555 1Q **Tunable erbium-doped fiber ring laser based on an all-fiber filter** [8555-35]
X. Ji, Z. Cao, Z. Zhang, T. Shui, W. Hao, B. Yu, Anhui Univ. (China)
- 8555 1R **Addressable wide dynamic range and high precision digital control device for adaptive liquid crystal microlenses array** [8555-37]
X. Chen, Huazhong Univ. of Science and Technology (China); S. Kang, Huazhong Univ. of Science and Technology (China) and Wuhan Polytechnic Univ. (China); X. Zhang, Huazhong Univ. of Science and Technology (China); A. Ji, Institute of Semiconductors (China); C. Xie, T. Zhang, Huazhong Univ. of Science and Technology (China)
- 8555 1S **Wide FOV receiving device for indoor visible light communication systems based on the MIMO principle** [8555-38]
X. Liu, Nanjing Univ. of Posts and Telecommunications (China) and Nanjing Xiaozhuang College (China); Z. Liang, X. Wang, Q. Ju, Nanjing Univ. of Posts and Telecommunications (China)
- 8555 1T **Three-dimensional modeling of nematic liquid crystal micro-optics structures with complex patterned electrodes** [8555-45]
X. Rong, Huazhong Univ. of Science and Technology (China); S. Kang, Huazhong Univ. of Science and Technology (China) and Wuhan Polytechnic Univ. (China); X. Zhang, Huazhong Univ. of Science and Technology (China); A. Ji, Institute of Semiconductors (China); C. Xie, T. Zhang, Huazhong Univ. of Science and Technology (China)
- 8555 1U **Photoelectric response performance of nano-graphene film over infrared substrates** [8555-46]
J. Gong, X. Zhang, F. Lin, Huazhong Univ. of Science and Technology (China); A. Ji, Institute of Semiconductors (China); C. Xie, T. Zhang, Huazhong Univ. of Science and Technology (China)
- 8555 1V **Micro-cavity lasers with directional emission** [8555-66]
C. Yan, Changchun Univ. of Science and Technology (China); Q. Wang, Nanjing Technological Univ. (Singapore); N. Yu, Harvard Univ. (United States)

DEVICES FOR PHOTONIC APPLICATIONS I

- 8555 1W **InGaN/GaN light-emitting diode on GaN/Si template with AlN/GaN superlattice as interlayer** [8555-30]
F. R. Hu, Y. J. Wang, H. B. Zhu, Z. C. Liang, Nanjing Univ. of Posts and Telecommunications (China)
- 8555 1Y **Thermal effects on interconnect crosstalk of optoelectronic transmitter modules** [8555-27]
I. A. Ukaegbu, J. Sangirov, B. Nakarmi, T.-W. Lee, M.-H. Cho, H.-H. Park, KAIST (Korea, Republic of)
- 8555 20 **Polymer planar lightwave circuit based hybrid-integrated coherent receiver for advanced modulation signals** [8555-29]
J. Wang, Y. Han, Z. Liang, Y. Chen, Nanjing Univ. of Posts and Telecommunications (China)
- 8555 21 **Error analysis and system implementation for structured light stereo vision 3D geometric detection in large scale condition** [8555-26]
L. Qi, X. Zhang, J. Wang, Y. Zhang, S. Wang, F. Zhu, Nanjing Univ. (China)

DEVICES FOR PHOTONIC APPLICATIONS II

- 8555 22 **Large area monolithic organic solar cells** [8555-32]
H. Jin, C. Tao, M. Hamsch, A. Pivrikas, M. Velusamy, M. Aljada, Y. Zhang, P. L. Burn, P. Meredith, The Univ. of Queensland (Australia)
- 8555 23 **Surface-corrugated microfiber Bragg grating (Invited Paper)** [8555-31]
F. Xu, J. Kou, W. Luo, Y. Lu, Nanjing Univ. (China)
- 8555 24 **Design of planar lightwave interleavers based on Echelle gratings structure** [8555-34]
W. Liu, B. Li, X. Dong, North China Univ. of Technology (China)

Author Index

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Yixin Zhang, Nanyang Technological University (Singapore)

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- 1 Plasmonic and Nano Materials/Devices I
Xuping Zhang, Nanjing University (China)
Bikash Nakarmi, KAIST (Korea, Republic of)
- 2 Plasmonic and Nano Materials/Devices II
Guanghui Wang, The Chinese University of Hong Kong
(Hong Kong, China)
- 3 Fiber and Guided-Wave Lasers/Semiconductor Devices I
Ho-Pui A. Ho, The Chinese University of Hong Kong
(Hong Kong, China)
Jianwei Wu, Chongqing Normal University (China)

- 4 Fiber and Guided-Wave Lasers/Semiconductor Devices II
Bikash Nakarmi, KAIST (Korea, Republic of)
Ho-Pui A. Ho, The Chinese University of Hong Kong
(Hong Kong, China)
- 5 Fiber and Guided-Wave Lasers/Semiconductor Devices III
Joel M. Therrien, University of Massachusetts Lowell (United States)
Guanghai Wang, The Chinese University of Hong Kong
(Hong Kong, China)
- 6 Devices for Photonic Applications I
Hai Ming, University of Science and Technology of China (China)
Douguo Zhang, University of Science and Technology of China
(China)
- 7 Devices for Photonic Applications II
Lixin Xu, University of Science and Technology of China (China)
Yuejiang Song, Nanjing University (China)

Quantum dot lasers and relevant nanoheterostructures

Alexey E. Zhukov*^a, Natalia V. Kryzhanovskaya^a, Artem V. Savelyev^a, Alexey M. Nadtochiy^a, Ekaterina M. Arakcheeva^a, Fedor I. Zubov^a, Vladimir V. Korenev^a, Mikhail V. Maximov^b, Yuri M. Shernyakov^b, Marina M. Kulagina^b, Ilia A. Slovinskiy^b, Daniil A. Livshits^c, Alexandros Kapsalis^d, Charis Mesaritakis^d, Dimitris Syvridis^d, Alexander Mintairov^c

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ABSTRACT

Spectral and power characteristics of QD stripe lasers operating in two-state lasing regime have been studied in a wide range of operation conditions. It was demonstrated that neither self-heating nor increase of the homogeneous broadening are responsible for quenching of the ground-state lasing beyond the two-state lasing threshold. It was found that difference in electron and hole capture rates strongly affects light-current curve. Modulation *p*-type doping is shown to enhance the peak power of GS lasing transition. Microring and microdisk structures ($D = 4\text{--}9\ \mu\text{m}$) comprising $1.3\ \mu\text{m}$ InAs/InGaAs quantum dots have been fabricated and studied by μ -PL and NSOM. Ground-state lasing was achieved well above room temperature (up to 380 K). Effect of inner diameter on threshold characteristics was evaluated.

Keywords: Quantum dots, semiconductor laser, microring resonator, two-state lasing

1. INTRODUCTION

For various applications, including optical data transmission, pumping of Raman amplifiers, aesthetic laser surgery, etc, efficient lasers operating around $1.3\ \mu\text{m}$ are requested. Lasers based on self-organized InAs/InGaAs quantum dots (QDs) offer an attractive combination of the required wavelength with extremely low threshold current density and high characteristic temperature. However, at sufficiently high currents a shorter-wavelength ($\lambda \sim 1.2\ \mu\text{m}$) band caused by the first excited-state (ES1) transition appears in the spectrum¹. Such a behavior is now referred to as two-state lasing. For a majority of applications two-state lasing has to be suppressed whereas the GS spectral component of the lasing spectrum has to be maximized. Analysis of QD laser behavior based on rate² and master³ equations predicts that optical power of the GS component reaches its maximal value at threshold of the two-state lasing and then persists. However a number of experimental facts revealed that the GS component declines down to its complete quenching^{4,5} due probably to laser self-heating in CW regime⁴ and/or increase of homogeneous broadening⁵ have been proposed. To clarify possible reasons of the GS lasing quenching we studied spectral and light-current characteristics of broad-area QD lasers.

Microdisks and microrings optical resonators comprising a III-V active region are promising candidates for light emitters to be integrated with silicon photonic circuits. Owing to a combination of a compact size and a high Q-factor, which can be achieved in such structures, ultralow threshold operation is expected. Although the majority of whispering gallery mode (WGM) resonators has been contained quantum-well active region composed of InP-based materials⁶, QDs may have certain advantages. These include attainability of $1.3\ \mu\text{m}$ emission in GaAs-based structures with high refractive index contrast, low temperature sensitivity, suppressed sidewall recombination rates⁷, making it possible to achieve lasing in resonators of small diameter. Since the first report⁸ on QD microdisk laser capable of operating at 77K, significant progress has been made toward high-temperature lasing. In particular, room-temperature lasing has been reported to date for microdisks of few microns in diameter⁹, whereas for relatively large microrings ($35\text{--}85\ \mu\text{m}$) lasing has been recently extended up to 50°C ¹⁰. In the present work we demonstrate ground-state lasing up to 107°C for optically pumped microring lasers (MRLs) having an outer diameter as small as $6\text{--}7\ \mu\text{m}$.

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2. TWO-STATE LASING AND ITS SUPPRESSION IN QD LASERS

2.1 Quenching of GS spectral component

Epitaxial structures comprising a single plane or multiple planes of InAs/InGaAs QDs were grown by molecular beam epitaxy. Stripe lasers of various cavity lengths were tested in pulse regime (300ns @ 2 kHz) on temperature-stabilized heatsink. An evolution of the lasing spectrum with increasing the pump current is shown in Figure 1,a for a 4-mm-long single-QD-plane laser at 17°C. The corresponding light-current characteristics (total output power and optical power of GS and ES1 spectral components of the spectrum) are presented in Figure 1,b. The ES1 band (around 1.18 μm) appears in the spectrum at approximately 3 A whereas the GS component reaches its maximum at 5A, well beyond the onset of two-state lasing. A complete quenching of the GS lasing is observed at 12 A.

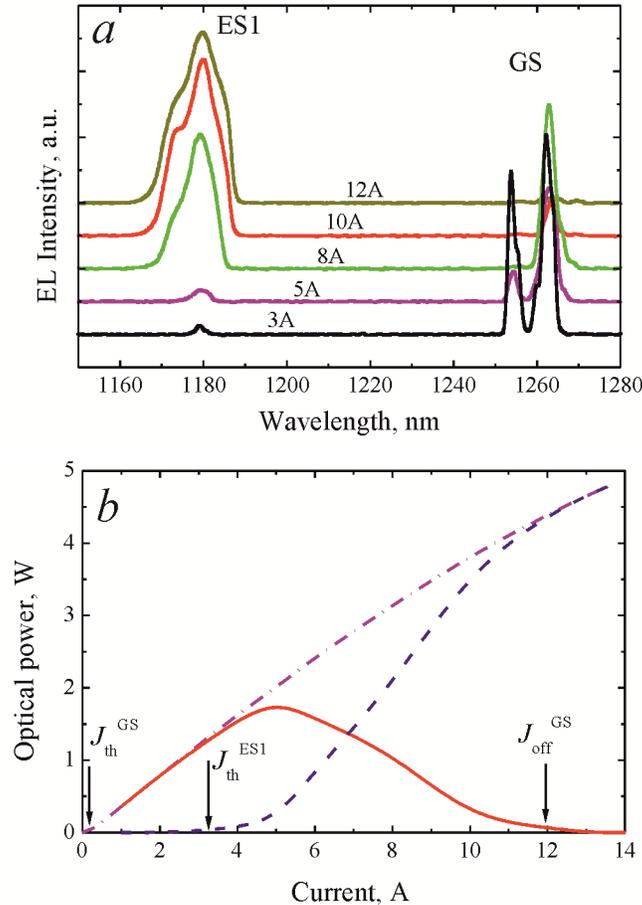


Figure 1. Lasing spectra at different currents (a); laser power (b): dashed-dotted curve – total (GS+ES1), solid curve – ground-state component (GS), dashed curve – first excited-state component (ES1).

As it is seen in Figure 1,a the GS band is split into two peaks (~ 1.254 and ~ 1.262 nm). According to M. Sugawara et al⁵ this splitting can be attributed to the homogenous broadening of the QD optical transition. They also suggested that the GS lasing quenching at high currents could be explained by increase of the homogenous broadening. In spite of this we found that the splitting is practically unchanged (6.5 ± 0.4 meV) as current increases up to 12 A. Therefore, the quenching can not be associated with the aforementioned reason. Moreover, spectral positions of the both GS peaks also remain very stable so that the current-induced red shift is only 0.4 nm. Such a shift corresponds to a negligible temperature increment of about 1°C which can not itself lead to suppression of the GS lasing because in this particular laser diode the GS lasing at low currents can be observed up to 68°C. Thus, the GS lasing quenching at high currents can not be attributed to self-heating of the active region as well.

2.2 Effect of difference in electron and hole relaxation rates

More sophisticated model that does not imply either the homogeneous broadening or self-heating effect is based on assumption of the asymmetry in charge carrier distribution in a QD¹¹. Energy separation of ground- and excited-state energy levels of holes is much smaller than kT that leads to a nearly equal probability of occupation of the hole levels. As a result, there is a competition for the “joint holes” between electrons of the ground-state and the excited-state levels. Because the ES1 electron level has a higher degeneracy as compared to the GS level, in the regime of two-state lasing the holes are effectively swept out from QDs because of their recombination with ES1 electrons. In its turn this leads to the quenching of the GS lasing as the pump current grows.

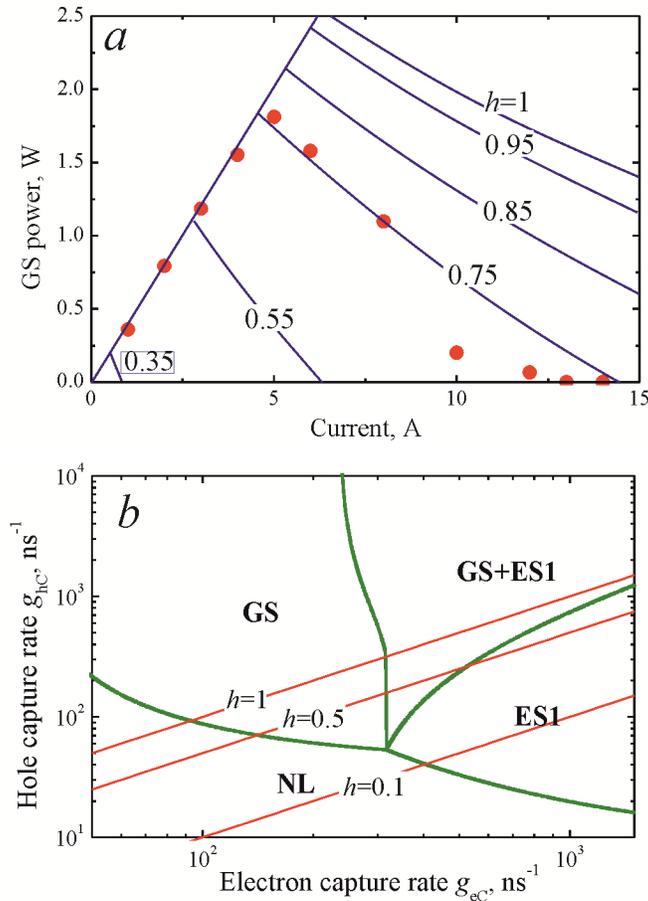


Figure 2. $L-I$ curves for ground-state component (a): circles – experiment; lines – calculation for different ratio of hole-to-electron relaxation rates (h). Operation diagram of QD laser: heavy lines separates regions of different lasing regimes (NL – no lasing, GS – pure ground-state lasing, GS+ES1 – two-state lasing, ES1 – pure excited-state lasing); thin lines correspond to different h values.

However, we found that the observed experimental data can not be quantitatively described if one takes into account only the above-mentioned asymmetry. Reasonable agreement between modeling results and experiment was achieved under assumption that electron and hole relaxation rates into QDs are different. More precisely, we assumed that the hole capture is slower than the electron one which makes the competition for holes more pronounced and leads to complete quenching of the GS lasing at lower pumps. Figure 2,a shows the calculated evolution of the GS power with the pump current. The results are shown for different ratio of the hole-to-electron relaxation rates h which is assumed to be independent of the injection rate. The best agreement of the model results with the experiment is found for $h = 0.75$. Lower rate of the hole relaxation is probably associated with their slower velocity in the matrix/wetting layer. Using the

extracted value of h we can also reproduce fairly well temperature dependences of the two-state lasing threshold and the current of the GS-lasing quenching.

Using the proposed model we are capable of calculating the operation diagram of QD laser as shown in Figure 2,b. The diagram depicts different regimes of the laser operation as a function of electron (g_{eC}) and hole (g_{hC}) capture rates: subthreshold regime of no lasing (NL), regime of lasing via GS optical transition (GS), two-state lasing regime (GS+ES1), regime of lasing via ES1 transition only (ES1). Depending on the ratio of hole-to-electron relaxation rates ($h = g_{hC}/g_{eC}$) and the total optical loss various scenarios of laser behavior can be realized. In particular, in case of sufficiently fast hole capture ($h = 1$ in Figure 2,b) the two-state lasing can persist so that the GS lasing peak is not completely suppressed even at very high injection levels.

2.3 Effect of p -type doping

Modulation p -type doping of QDs may noticeably improve temperature stability of the threshold current¹². We found that p -doping affects the two-state lasing behavior as well. Temperature dependences of the two-state lasing threshold current as well as the ground-state lasing threshold current are presented in Figure 3 for two 0.6-mm-long diodes of similar design (10 planes of InAs/InGaAs QDs): one with undoped active region and another with modulation doping (~ 10 acceptors per QD). The GS-lasing thresholds measured at room temperature are nearly equal in both structures (~ 0.35 A). At the same time, the onset of the two-state lasing is significantly shifted to higher currents in the p -type doped laser (~ 5.5 A) as compared to its undoped analogue (~ 1.1 A). Light-current curve (insert of Figure 3) demonstrates that the maximum optical power of the GS spectral component reaches 3.6 W in the laser with p -type doping, while it is about 2.4 W in the undoped counterpart. Another finding is that the temperature interval, where GS lasing can be achieved, extends to higher temperatures in the p -doped structure (from 55 to 100°C).

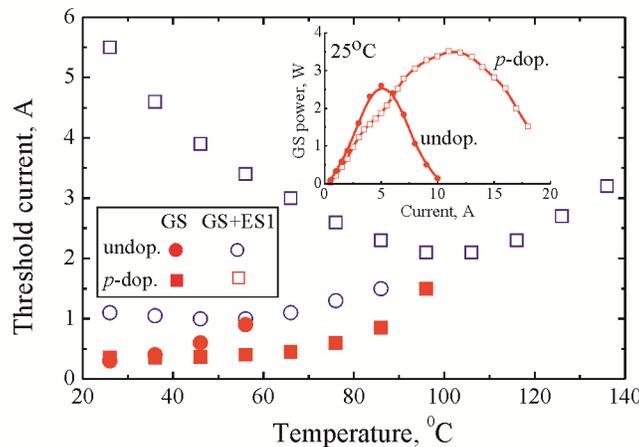


Figure 3. Threshold vs temperature for ground-state lasing (solid symbols) and two-state lasing (open symbols) in lasers with undoped (circles) and p -type doped (squares) QDs. Insert: power of the GS-line vs current.

2.4 Comparison of lasing and spontaneous emission spectra

Spontaneous emission spectra may provide additional information on peculiarities of the two-state lasing. We studied QD lasers having 4 cleaved facets where both lasing and spontaneous emission can be simultaneously detected as shown in Figure 4. At least five peaks of different origin are easily resolved: two narrow peaks of lasing emission via ground-state (1264.3 nm) and first excited-state (1179.8 nm) transitions and three broad peaks of spontaneous emission via ground-state (1264.0 nm), first excited (1172.0 nm) and second excited-state (1108.4 nm) transitions. The characteristic feature is that the GS lasing peak nearly coincides with the peak position of GS spontaneous emission. This implies that the GS lasing arises from QDs of the most probable (mean) size. At the same time ES1 lasing peak is noticeably redshifted with respect to the peak position of ES1 spontaneous emission indicating that QDs, which size is larger than the mean one, are chiefly responsible for the ES lasing. Similar behavior was observed in a wide interval of current density.

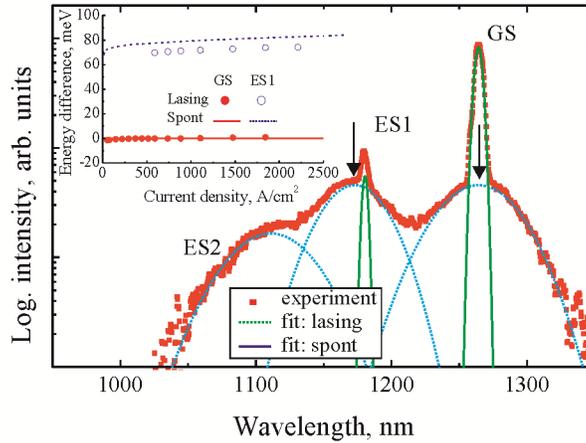


Figure 4. Emission spectrum: squares – experiment, solid curves – lasing emission, dotted curves – spontaneous emission. Insert: peak position vs current density: solid circles – GS lasing, open circles – ES1 lasing, solid curve – GS spontaneous emission, dotted curve – ES1 spontaneous emission.

3. MICRORING STRUCTURES

3.1 Experiment

An epitaxial structure was grown by molecular beam epitaxy on semi-insulating GaAs(100) substrate. An active region comprises five layers of InAs/In_{0.15}Ga_{0.85}As QDs separated by 30-nm-thick GaAs spacers. The active region was inserted into a 220-nm-thick GaAs waveguiding layer confined by 20-nm-thick Al_{0.3}Ga_{0.7}As barriers. A 400-nm-thick Al_{0.98}Ga_{0.02}As cladding layer was grown beneath the waveguiding layer. Microrings were defined by photolithography and Ar⁺-etching. The outer diameter was varied in different structures from $D = 4$ to $9 \mu\text{m}$. The inner diameter ranges from $d = 0$ (microdisks) to $d \approx 0.8D$. Finally, the cladding layer was selectively oxidized into (AlGa)_xO_y. Typical microphotograph of the resonator structure is shown in Figure 5.

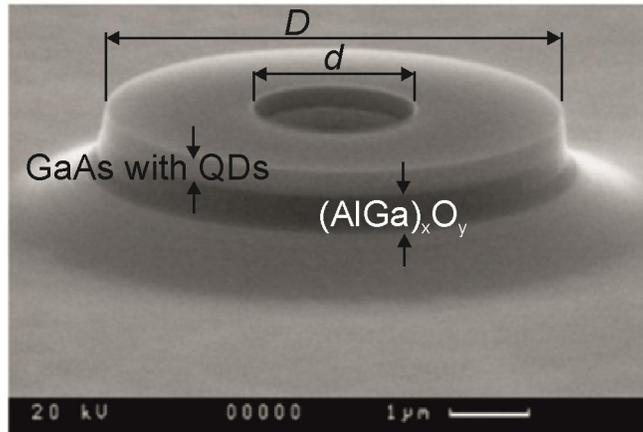


Figure 5. SEM image of QD microring laser ($D = 6 \mu\text{m}$, $d = 2 \mu\text{m}$).

For optical experiments a CW-operating YAG:Nd laser ($\lambda = 532\text{nm}$) was used together with a cooled Ge *pin*-diode. Measurements at elevated temperatures were performed with the structures mounted onto a heated holder equipped with a temperature controller. Low temperature measurements were done in a flow cryostat.

3.2 Low-temperature measurements

An example of luminescence spectrum taken at 77 K from 6 μm -ring with 2 μm inner diameter is shown in Figure 6. Four series of whispering gallery modes of different radial order are clearly observed. All modes presented in the optical spectrum were identified by means of 2D-axisymmetric analysis. The dominant modes are of $n=2$ and 3 order. Significant overlap of many modes exists (e.g. around 1190.8 nm where 3 modes are close together).

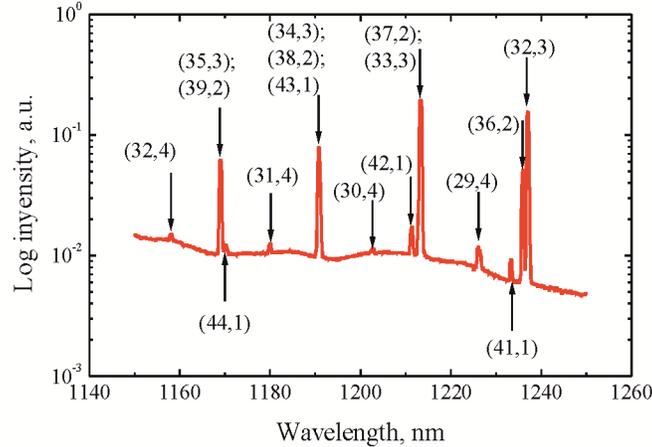


Figure 6. Low-temperature luminescence spectrum of the microring. Estimated mode orders $\text{TE}_{m,n}$ are indicated near the peaks.

3.3 Near-field scanning optical microscopy.

Spatial distribution of light intensity inside the microresonators was studied by means of near-field scanning optical microscopy (NSOM). Several typical NSOM images are presented in Figure 7. Characteristic WGM patterns are clearly seen. Depending on spectral position of the luminescence peaks, NSOM images reveal modes of different radial and azimuthal order.

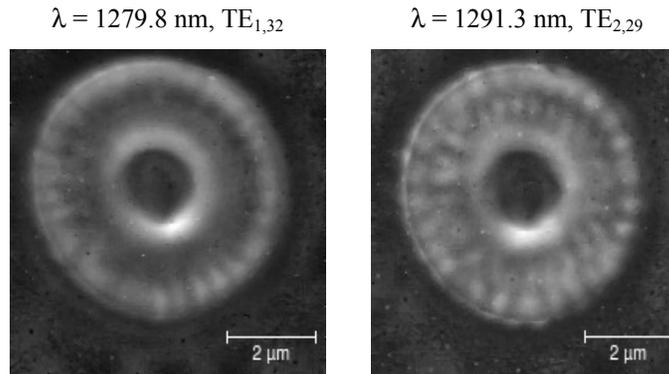


Figure 7. NSOM images demonstrating WGM modes of different orders in the microring resonator.

3.4 Room-temperature measurements.

A representative room-temperature $\mu\text{-PL}$ spectrum taken under low excitation is shown in the left insert of Figure 8. Full width at half maximum for resonant peaks varies from 0.143 to 0.234 nm giving the quality factor of about 9000.

The threshold power for the microring/microdisk structures was estimated from a light-light curve of the dominant mode. An example is presented in Figure 8 where a characteristic knee is clearly seen. In this particular case ($D = 7 \mu\text{m}$,

$d = 3.4 \mu\text{m}$) the threshold power is 0.37 mW. No correction was made to take into account partial light reflection from the surface or waste of the excitation power in the inner area of microring structures. Overall the threshold power at room temperature in different structures ranges from few tenths of mW to few mW. From one to three modes were usually observed in room-temperature lasing spectra (see right insert of Figure 8).

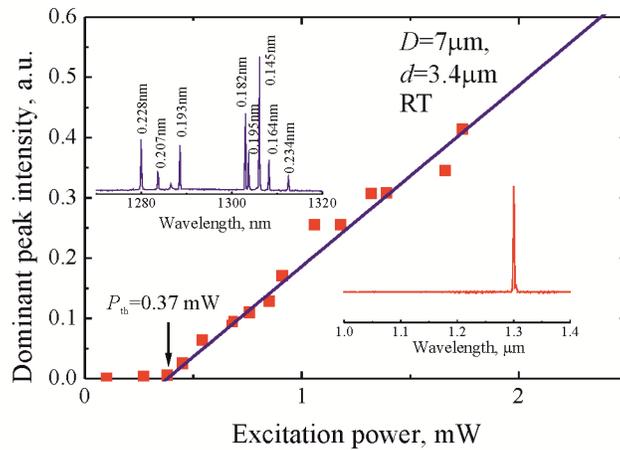


Figure 8. Intensity of the dominant mode against excitation power (symbols). Curve is a guide to the eye. Insert: luminescence spectrum below threshold (left) and above threshold (right).

Room-temperature threshold characteristics of the microstructures with different inner diameters were compared. In most cases the threshold power (absolute value) decreases by approximately 30-40% as the inner diameter increases from 0 (disk) to 0.3-0.6 D , see Figure 9. Further ring thinning results in rapid growth of the threshold. As for the effect of the outer diameter, the lowest threshold of 0.37-0.4 mW was found in microrings having an outer diameter of 6–7 μm . Both larger and smaller microrings demonstrate higher threshold power as shown in the insert of Figure 9.

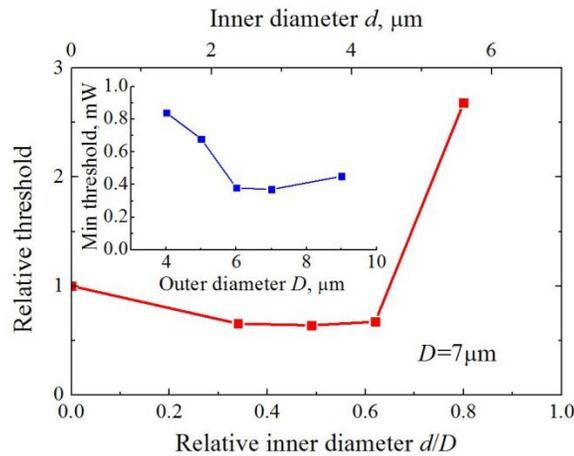


Figure 9. Room-temperature threshold (normalized to the threshold of the microdisk structure) as a function of inner diameter. Insert: the lowest threshold against the outer diameter.

3.5 High-temperature measurements

Threshold power increases super-exponentially with temperature. Around room temperature the characteristic temperature was estimated to be $\sim 60\text{--}75 \text{ K}$. In most cases, lasing can be observed up to $80\text{--}90^\circ\text{C}$ whereas the highest temperature of lasing was found to be as high as 107°C , Figure 10. To the best of our knowledge this is the highest

temperature ever reported for 1.3 μ m QD MRLs. Below room temperature the threshold is nearly unchanged or even slightly increases. Temperature variation of the lasing wavelength is summarized in Figure 10. Spectral position of the ground-state optical transition of quantum-dot luminescence is also shown for comparison. It is seen that the lasing wavelength is quite stable (~ 0.05 nm/K) within relatively wide temperature intervals (e.g. from 20 to 40 $^{\circ}$ C and then from 50 to 90 $^{\circ}$ C) where a certain WGM mode remains the dominant one. Abrupt changes of the lasing wavelength (e.g. around 40-50 $^{\circ}$ C) are due to hopping of the dominant mode.

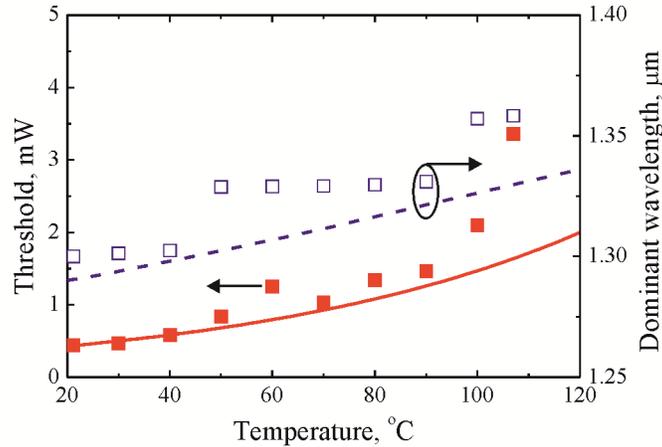


Figure 10. Temperature dependences of the threshold power (solid symbols) and wavelengths of the dominant mode (open symbols). QD ground-state optical transition against temperature (dashed curve) is also shown. Solid curve is exponential fit with $T_0=65$ K.

4. CONCLUSIONS

Quantum dot lasing structures of two sorts both emitting around 1.3 μ m were studied: broad-area diode lasers and optically pumped microresonators.

Broad-area lasers were used for detailed investigation of the two-state lasing phenomenon and, in particular, quenching of the ground-state lasing emission that observed at high currents. It was demonstrated that the most probable reason for the GS lasing quenching is asymmetry of electrons and holes carrier distributions. Additionally, difference in capture rates of electrons and holes has to be taken into consideration. We also found that the GS-component reaches its maximum beyond the threshold of the two-state lasing and that different groups of QDs are responsible for GS- and ES1-lasing in the two-state lasing regime. Finally, we demonstrated that *p*-type modulation doping of QDs leads to noticeable suppression of the ES1-lasing thereby resulting in enhancement of peak power of the GS spectral component.

Microrings and microdisks of few micrometers in diameter were made by ion etching and selective oxidation with Q-factor of about 9000. Whispering gallery modes of second and third radial orders dominate the luminescence spectrum. Nearly single-mode lasing was observed at elevated temperatures. The lowest threshold (around 0.4 mW at RT) was found in microdisks of intermediate diameter (6-7 μ m) with approximately 50% inner aperture. The highest temperature was found to be 107 $^{\circ}$ C and the threshold was in mW-range.

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